EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S17	6	15/88.2,102.ccls. and (multiple or plurality or several or (first near10 second)) near10 (brush$3 or head) near10 (rotat$3) near10 (gear$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	ON	2007/03/20 10:40
L1	8	"6286525"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	ON	2007/03/20 10:40
L2	13	("5361449" | "5518542" | "5651160" | "5868854" | "5868866" | "5893381" | "5893756").PN. OR ("6286525"). URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2007/03/20 10:55
L3	50	(134/181,88,902.ccls. or 15/77, 102,88.2) and (wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near5 (wash adj head or head or nozzle or brush or wash$head) same (motor or engine or driv$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/03/20 11:19
L4	2807	(wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near5 (wash adj head or head or nozzle or brush or wash$head) same (motor or engine or driv$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	ON	2007/03/20 11:21
L5	1018	(wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near4 (wash adj head or head or nozzle or brush or wash$head) near10 (motor or engine or driv$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT	OR	ON	2007/03/20 11:31
L6	991	(wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near4 (wash adj head or head or nozzle or brush or wash$head) near10 (motor or engine or driv$3)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT	OR	ON	2007/03/20 11:53
L8	0	"655224".ap.	USOCR	OR	ON	2007/03/20 11:54

L9	1	"655224".ap.	US-PGPUB	OR	ON	2007/03/20 11:55
L7	27	(wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near4 (wash adj head or head or nozzle or brush or wash$head) near10 (motor or engine or driv$3)	USOCR	OR	ON	2007/03/20 11:56
L10	2	134/94.1,103.2.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near4 (wash adj head or head or nozzle or brush or wash$head) near10 (motor or engine or driv$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/03/20 11:57
L11	15	134/94.1,103.2,148,153,198.ccls. and (wafer or semiconductor or substrate or workpiece) near10 (multiple or plurality or several or (first and second)) near4 (wash adj head or head or nozzle or brush or wash$head) near10 (motor or engine or driv$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/03/20 11:58

3/20/2007 12:06:22 PM

Page 2

C:\Documents and Settings\shusband\My Documents\EAST\Workspaces\10655224 wafer cleaner multiple rotation axes and wash hea

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L12	1	(wafer and base and driving and device and couple and axes and second and transmission and third and motor and drive and rotate and rotation and module and top and multiple and bottom and connected and path).clm.	US-PGPUB; USPAT; USOCR	OR	ON	2007/03/20 12:08